Supplemental Information

Comparative Study on the Impacts of Anhydrous and Hydrous H_2O_2 on ALD Hafnium Oxide Growth on Titanium Nitride Surface

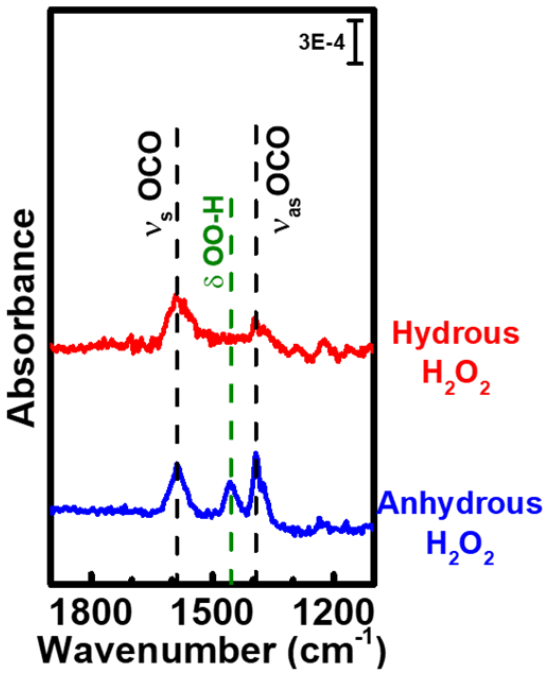

Figure 1. *in-situ* IR spectra, between 1100 cm-1 and 1900 cm-1, of hydrous and anhydrous H_2O_2 with reference to the TDMA-Hf modified TiN surface.

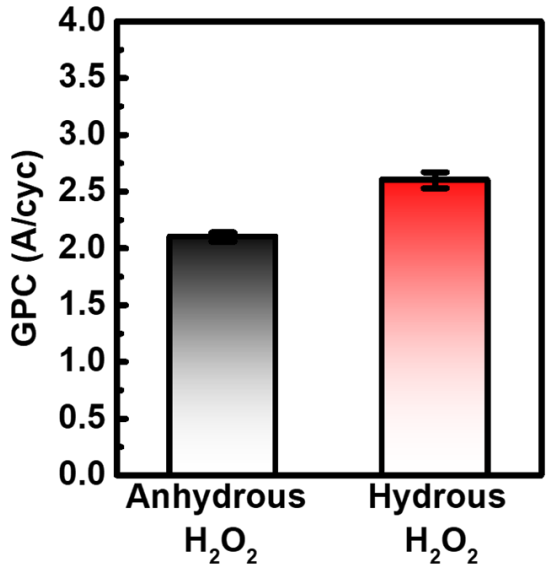

Figure 2. The growth per cycle (GPC) of HfO_2 thin films achieved using anhydrous and hydrous H_2O_2 as the oxidant source.